Electronic Supplementary Information:

Synthesis and Chemical Transformation of Ni Nanoparticles Embedded in Silica

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Growth of SiO₂ NPs without Ni NPs:



Figure S1. TEM images (common scale bar) for aliquots from the synthesis of SiO_2 NPs after (a) 1 hour, (b) 2 hours, (c) 4 hours, (d) 8 hours, (e) 42 hours, and (f) 48 hours. (g) Plot of the dependence of the average SiO_2 NP diameter on the growth time.

Size Distribution of Ni NPs in SiO₂-Ni NPs at t = 0 Hours



Figure S2. Histogram of diameters of Ni NPs within SiO₂-Ni NPs at t = 0 hours, corresponding to Figure 1a.

Oxygen EDS Maps for SiO₂-Ni NPs:



Figure S3. EDS maps (common scale bar) of O for (a) SiO₂-Ni NPs, (b) oxidized SiO₂-Ni NPs, (c) oxidized then reduced SiO₂-Ni NPs, (d) reduced SiO₂-Ni NPs, and (e) reduced then oxidized SiO₂-Ni NPs.